

STRUCTURE AND METHOD FOR DETERMINING EDGES  
OF REGIONS IN A SEMICONDUCTOR WAFER

Abstract of the Disclosure

5 A method for electrically determining in a semiconductor wafer the location of edges of a well that underlies an insulating layer that includes forming in the wafer before forming of the well and the insulating layer a plurality of conductive stripes will that pass under the future insulating layer and extend to varying distances under the insulating layer so as to include stripes that will penetrate an edge to be located so as to form a low resistance connection thereto and stripes that will fall short of an edge to be located. From the stripes of minimum penetration that make low resistance can be determined the location of the well edges.